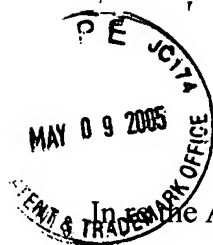


JPW



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In the Application of:

**KANAYA et al.**

Serial No.: TBA 10/602,764

Filed: June 25, 2003

For: Semiconductor Device Having Ferroelectric Capacitor and Hydrogen Barrier Film and Manufacturing Method Thereof

Atty. Docket No.: 002372.00043

Group Art Unit: TBA

Examiner: TBA

**AMENDMENT**

Commissioner for Patents  
Customer Service Window  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314

Sir:

In response to the office action mailed February 10, 2005, please enter the following amendments and remarks into the file of the instant application. No fees are believed due in connection with this paper. If any fees are required or an overpayment made, the Commissioner is authorized to charge or credit our deposit account no. 19-0733 as required.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 9 of this paper.